

Docket No. 50654

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicants: T. Adams

Serial No: 09/825,070

Examiner: S. Lee

Filed: April 2, 2001

Group Art Unit: 1752

For: PHOTORESIST COMPOSITION AND USE OF SAME

ASSISTANT COMMISSIONER FOR PATENTS  
WASHINGTON, D.C. 20231

Sir:

**PRELIMINARY AMENDMENT**

Please amend the above identified application as follows.

**IN THE SPECIFICATION**

At page 1 of the application, immediately after the title, please add the following sentence as the first line of text of the application:

a' --The present application claims the benefit of U.S. provisional application number 60/194,287, filed April 3, 2000, which is incorporated herein by reference.--

**IN THE CLAIMS**

Please cancel without prejudice non-elected claims 1-16 and 28-30.

17. (amended) A method for treating a microelectronic wafer substrate, comprising:
- a) applying a layer of a positive-acting photoresist composition on the microelectronic substrate, the photoresist composition comprising a photoactive component and a polymer that comprises 1) groups reactive to crosslinking; and 2) photoacid-labile groups; and
- a2  
b2